

JUL 07 2004

Patent Application

2771-506

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

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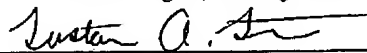
In re United States Patent Application of:	)	Docket No.:	ATMI-506 (7486)
Applicant:	)	Examiner:	WONG, Edna
Application No.:	)	Art Unit:	1753
Date Filed:	)	Confirmation No.:	9419
Title:	)	Customer No.:	25559
SYSTEM FOR IN-SITU			
GENERATION OF FLUORINE			
RADICALS AND/OR			
FLUORINE-CONTAINING			
INTERHALOGEN (XF <sub>n</sub> )			
COMPOUNDS FOR USE IN			
CLEANING SEMICONDUCTOR			
PROCESSING CHAMBERS			

FACSIMILE TRANSMISSION CERTIFICATEATTN: Examiner Edna WONGFax No. (703) 872-9306

I hereby certify that this document is being filed in the United States Patent and Trademark Office, via facsimile transmission to Mail Stop Amendment, Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22313-1450, on July 7, 2004, to United States Patent and Trademark Office facsimile transmission number (703) 872-9306.

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Number of Pages (including cover)



Tristan Fuierer

July 7, 2004

Date

RESPONSE TO APRIL 9, 2004 OFFICE ACTION  
IN UNITED STATES PATENT APPLICATION NO. 10/065,219

Commissioner for Patents  
PO Box 1450  
Alexandria, VA 22313-1450

Sir:

This responds to the April 9, 2004 Office Action in the above-identified application.

Patent Application  
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Please amend the claims of the application as set out in the following **Section I (Amendments to the Claims)**.

Please amend the drawings of the application as set out in the following **Section II (Amendments to the Drawings)**.

Remarks addressing the various issues raised in the April 9, 2004 Office Action are set out in **Section III (Remarks)** hereof.